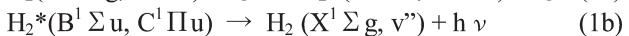
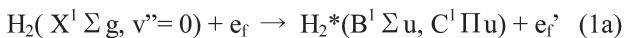


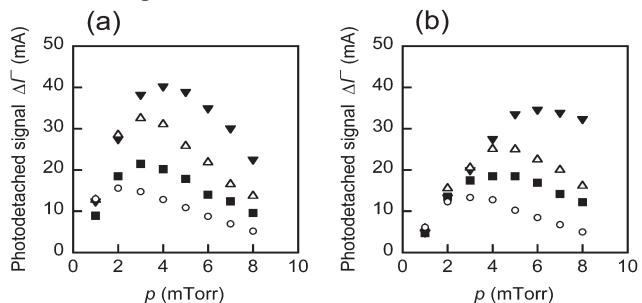
## §4. Production Mechanism of D<sup>-</sup> Ions and Evaluation of D<sup>-</sup> Ion Current Extraction

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In a tandem volume source, H<sup>-</sup> ions are generated by the dissociative attachment of slow plasma electrons e<sub>S</sub> ( $T_e \sim 1\text{eV}$ ) to highly vibrationally excited hydrogen molecules H<sub>2</sub>(v'') (effective vibrational level v''  $\geq 5 \sim 6$ ). These H<sub>2</sub>(v'') are mainly produced by collisional excitation of fast electrons e<sub>f</sub> with optimum energy of about 40 eV. Namely, H<sup>-</sup> ions are produced by the following two step process, i.e. H<sub>2</sub>(v'') production and H<sup>-</sup> formation:



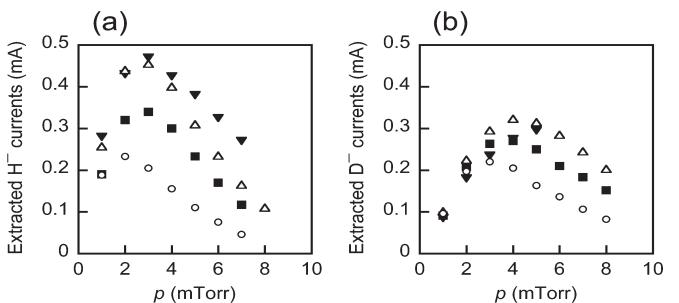
Production process of D<sup>-</sup> ions is believed to be the same as that of H<sup>-</sup> ions described above. We have studied relationship between negative ion production (i.e. H<sup>-</sup> and D<sup>-</sup> ions)<sup>1,2)</sup> and plasma parameters controlled by the magnetic filter (MF). Varying the intensity of the MF, axial distributions of  $T_e$  and  $n_e$  in both H<sub>2</sub> and D<sub>2</sub> plasmas are changed strongly in the downstream region, i.e. the extraction region<sup>3,4)</sup>.



**Fig. 1.** Pressure dependence of negative ion densities in the vicinity of the extraction electrode: (a) H<sup>-</sup> density and (b) D<sup>-</sup> density. Parameter is the magnetic field intensity  $B_{\text{MF}}$  of the MF,  $B_{\text{MF}}=50\text{G}(\blacktriangledown)$ ,  $80\text{G}(\triangle)$ ,  $120\text{G}(\blacksquare)$  and  $150\text{G}(\circ)$ . Experimental conditions are as follows: discharge voltage  $V_d = 70\text{ V}$  and discharge current  $I_d = 10\text{ A}$ .

Figure 1 shows the pressure dependence of negative ion densities in (a) H<sub>2</sub> and (b) D<sub>2</sub> plasmas. In both cases, as described above, the negative ion densities are varied due to the change in plasma conditions with changing the magnetic field intensity  $B_{\text{MF}}$  of the MF. As shown clearly, there are some optimum pressures. With increasing gas pressure, negative ion densities increase in their magnitude, reach the maximum value, and then, decrease. Decreasing the  $B_{\text{MF}}$ , the optimum pressure  $p_{\text{opt}}$  shifts to higher pressure. For D<sup>-</sup> production,  $p_{\text{opt}}$  is changed from 3 to 6 mTorr. On the other hand, for H<sup>-</sup> production,  $p_{\text{opt}}$  is from 2 to 4 mTorr.

Optimum pressure in D<sub>2</sub> plasmas is slightly higher than one in H<sub>2</sub> plasmas.



**Fig. 2.** Pressure dependence of extracted (a)H<sup>-</sup> and (b)D<sup>-</sup> currents, corresponding to the negative ion densities shown in Fig. 1, where extraction voltage  $V_{\text{ex}} = 1.5\text{ kV}$ .

The corresponding extracted negative ion currents are shown in Fig. 2. As a whole, pressure dependence have the same feature as ones of negative ion production shown in Fig. 1 although details are slightly changed.

On negative ion production, intensity of the VUV emission caused by the process (1b) is measured. The values of integrated intensities in the source region are increased with increasing gas pressure and the  $B_{\text{MF}}$ . As shown in Fig. 1, the H<sup>-</sup> and D<sup>-</sup> densities vary with the  $B_{\text{MF}}$ . It is noted that the integrated intensity of the VUV emissions and the H<sup>-</sup> and D<sup>-</sup> densities vary in opposite directions, respectively, when the  $B_{\text{MF}}$  is varied<sup>3)</sup>. Numerical calculations show that the VUV emissions associated with the process (1b) are a function of fast primary electrons, i.e. its density and behavior<sup>4)</sup>. With increasing the  $B_{\text{MF}}$ , fast electron density in the source region is increased and then the collisions with process (1b) are also increased. Then, the intensity of VUV emission increases with the  $B_{\text{MF}}$  as ones observed in the present experiment.

According to the results shown in Figs. 1 and 2 and related discussions, our present picture on negative ion production is as follows: In the present experimental conditions with low-pressure, electron-neutral collision mean free paths for destruction of the vibrationally excited molecules (i.e. ionization and dissociation collisions) are a few tens of centimeters. Therefore, sufficient amount of H<sub>2</sub>(v'') and D<sub>2</sub>(v'') are transported to the extraction region, although H<sub>2</sub>(v'') and D<sub>2</sub>(v'') are produced by the collisions between the ground state molecules and fast primary electrons in the source region. The negative ions are produced by the process (2) of slow plasma electrons to H<sub>2</sub>(v'') and D<sub>2</sub>(v'') in the extraction region. Namely, negative ion production is rate-determined by the plasma parameters in the extraction region.

## References

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